

AMENDMENTS TO THE CLAIMS

With this Amendment, claims 1, 3, 8, 10, 11 and 13 have been amended and claims 2 and 12 have been canceled. This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A continuous plating system comprising:
first and second vertically oriented, spaced anodes that define a plating area;
first and second vertically oriented upper shields positioned in the plating area to define
an elongated upper channel-plating;
formed by two upper shields and an elongated lower channel formed by twofirst and
second vertically oriented lower shields positioned in the plating area to define an
elongated lower channel, wherein the first and second lower shields are positioned
relative to the first and second upper shields to define a gap between the first
upper and first lower shields and a gap between the second upper and second
lower shields;[[-]]
~~wherein each channel is separated by a gap between the upper and lower shields, wherein~~
~~a part clamp configured to move one or more parts through the plating area, the~~
~~part clamp being positioned relative to the plating area such that an upper portion~~
~~of a part to be plated is positioned in the upper channel, a lower portion of the part~~
~~is positioned in the lower channel and a height of the gaps is less than the a height~~
~~of the one or more parts being plated, and wherein the shortest distance from the~~
~~part being plated to a channel wall is less than the shortest distance between the~~
~~channel wall and an anode; and~~
a plating solution horizontal sparger comprising a series of inlets positioned below the
plating area and oriented to direct ~~any~~ plating solution flowing through the inlets
directly into one and towards another of the upper and lower channels.
2. (Cancelled)

3. (Currently Amended) The system of claim 2 wherein the sparger directs ~~any~~ plating solution flowing through the inlets ~~towards the cathode~~ in a plane substantially coplanar with the plating shield~~seathode~~.

Claims 4-7. Canceled.

8. (Currently Amended) The system of claim 1 wherein each of the upper channel and lower channel ~~[[have]]~~has a width less than or equal to one inch.
9. (Previously Presented) The system of claim 1 wherein the horizontal sparger directs any plating solution flowing through the inlets into the lower channel and towards the upper channel.
10. (Currently Amended) The system of claim 1 wherein each of the upper channel and lower channel ~~[[have]]~~has a width less than or equal to 0.5 inches.
11. (Currently Amended) The system of claim 1 ~~wherein each of the upper channel and lower channel has a width less than or equal to 0.5 inches, and~~ further comprising a plurality of part ~~holding~~ clamps electrically coupled to a power source and positioned within the upper channel or the lower channel.
12. (Canceled)
13. (Currently Amended) The system of claim 1 wherein ~~the upper channel and lower channel are separated by a distance and~~ at least one of the upper channel and lower channel ~~[[are]]~~is adapted to be moved to vary the ~~distance~~ height of the gaps.

Claims 14-18. Canceled.

19. (Previously Presented) The system of claim 1, wherein the gap is 20 percent of the height of the part being plated.